

Title (en)
POLISHING APPARATUS AND POLISHING METHOD

Title (de)
POLIERVORRICHTUNG UND POLIERVERFAHREN

Title (fr)
APPAREIL ET PROCÉDÉ DE POLISSAGE

Publication
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Application
EP 05781363 A 20050901

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Abstract (en)
[origin: WO2006025507A1] A polishing apparatus and a polishing method. The polishing apparatus capable of accurately chamfering the end face parts of a large-sized substrate is installed on a table unit in which the substrate is placed. The substrate is fixedly held on the table unit (60) under a specified reference condition. A first polishing unit (40a) comprises a polishing grinding wheel polishing the end faces of the substrate held on the table unit (60) and a substrate side edge part support means supporting the side edge part lower surface of the substrate near the end faces of the substrate polished by the polishing grinding wheel. The first polishing unit (40a) is moved by a first polishing unit moving means (85A) along the end faces of the substrate together with the substrate side edge part support means under the condition that the polishing grinding wheel polishes the end faces of the substrate.

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Citation (search report)
• No further relevant documents disclosed
• See references of WO 2006025507A1

Cited by
CN109333317A; CN112476151A; EP2995994A3; US9884448B2; US11904521B2

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